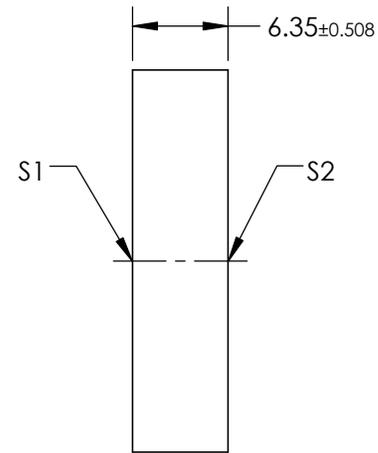
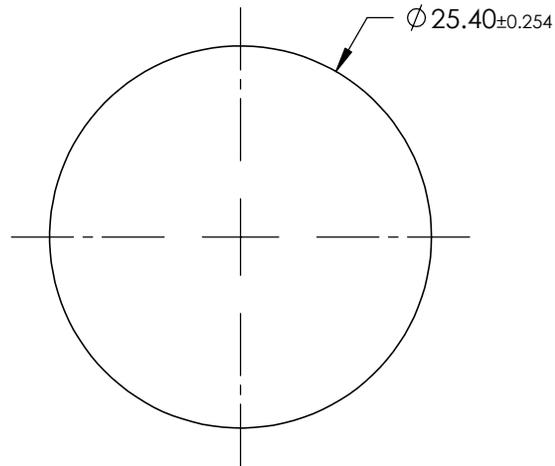


NOTES:

1. SUBSTRATE:  
SINGLE CRYSTAL SILICON
2. COATING (APPLY ACROSS COATING APERTURE):  
Mo/Si MULTILAYER; TOP LAYER Si  
  
S1: R(ABS) > 65% (S-POLARIZATION) @ 13.5nm; FWHM 0.98nm  
S2: NONE
3. WAVELENGTH RANGE (nm): 12.92 - 13.90

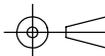
FOR INFORMATION ONLY:  
DO NOT MANUFACTURE  
PARTS TO THIS DRAWING



SPECIFICATIONS SUBJECT TO CHANGE WITHOUT NOTICE  
DIMENSIONS ARE FOR REFERENCE ONLY

**EO**<sup>®</sup> Edmund Optics<sup>®</sup>

	S1	S2
SHAPE	PLANO	PLANO
SURFACE ROUGHNESS	< 3 Å RMS	N/A
SURFACE FLATNESS	λ/10	N/A
BEVEL	PROTECTIVE AS NEEDED	PROTECTIVE AS NEEDED

THIRD ANGLE PROJECTION 

ALL DIMS IN mm

TITLE	13.5nm, 25.4mm DIA, 45° AOI, EUV FLAT MIRROR		
DWG NO	38760	SHEET	1 OF 1